

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	25455	(detect\$3 or sens\$3 or measur\$5 or determin\$5) near4 (lens or (projection adj (optical or device)) or mirror) near4 (position or location or displac\$5)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:20
L3	25890	(detect\$3 or sens\$3 or measur\$5 or determin\$5) near4 (lens or (projection adj (optical or device)) or mirror) near4 (position or location or displac\$5 or orientation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:25
L4	39300	((mask or reticle) or (substrate or wafer)) near4 (control\$4 or move or moving or moved or moves or driv\$3 or adjust\$4) near4 (position or location or direction)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:23
L5	39300	((mask or reticle) or (substrate or wafer)) near4 (control\$4 or move or moving or moved or moves or driv\$3 or adjust\$4) near4 (position or location or direction)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:24
L6	1736	3 and 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:24
L7	1491	((lens or (projection adj (optical or device)) or mirror) near4 (position or location or displac\$5 or orientation)) same 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:56
L8	645	3 and 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:29
L9	302960	lithography or photolithography or (project\$3 near4 (radiation or light or illumination))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:30

L10	540	8 and 9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:38
L13	419	3 same 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/30 15:56

OK
10/30/05.